Notice of Allowability	Application No.	Applicant(s)	Applicant(s)	
	10/601,090	VISCOR ET AL.	VISCOR ET AL.	
	Examiner	Art Unit	. N	
	Zia R. Hashmi	2881	8	
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.				
1. This communication is responsive to <u>8/19/2004</u> .				
2. The allowed claim(s) is/are <u>1-58</u> .				
3. A The drawings filed on 20 June 2003 are accepted by the Examiner.				
 4. Acknowledgment is made of a claim for foreign priority ur a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority do International Bureau (PCT Rule 17.2(a)). * Certified copies not received: 	been received. been received in Application	on No	ation from the	
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		e a reply complying with the re	quirements	
5. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.				
 6. CORRECTED DRAWINGS (as "replacement sheets") must be submitted. (a) including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d). 				
7. DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT	SIT OF BIOLOGICAL MAT FOR THE DEPOSIT OF BIO	ERIAL must be submitted. OLOGICAL MATERIAL.	Note the	
Attachment(s) 1. ☐ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/O Paper No./Mail Date	6. Interview S Paper No. 08), 7. Examiner's	oformal Patent Application (PT Summary (PTO-413), /Mail Date : Amendment/Comment Statement of Reasons for Allo	·	

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DETAILED ACTION

Allowable Subject Matter

- 1. An "Amendment" was received on August 19, 2004, in response to Office Action of May 19, 2004.
- 2. Claims 1-58 are allowed.
- 3. The following is an examiner's statement of reasons for allowance:

With respect to independent claims 1, 9, 16, 32, 41, 51, and 58, prior art fails to disclose a planar electron emitter (PEE) system for lithography, which includes a PEE having a first and second electrically conducting layer that emits electrons with an insulating layer disposed between the two layers. The second conducting layer emits electrons when held at an electrical potential that is sufficiently positive with respect to an electrical potential applied to the first electrically conducting layer. A source of electric potential is electrically connected to the conducting layers so as to impose an electrical potential across the insulating layer. The source of electric potential is adapted so that a polarity of the electrical potential difference between the first and the second electrically conducting layers is reversible. The system also includes a temperature control unit thermally connected to the planar electron emitter for controlling its temperature, a substrate mount for holding a substrate having a resist layer facing the planar electron emitter, and an adjustable stage. The mount is fixed relative to the adjustable stage. The adjustable stage is adapted to move a wafer, when the mount holds a wafer, relative to the planar electron emitter so that successively different

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portions of resist on the wafer are exposed to electrons emitted from the second electrically conducting layer. The PEE is claimed to have a lifetime in excess of one million exposure shots of approximately 100 msec.

Conclusion

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- 4. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments of Statement of Reasons for Allowance".
- 5. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact Electronic Business Center (EBC) at 866-217-9197 (toll-free).
- 6. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Zia Hashmi whose telephone number is (571) 272-2473. The examiner can normally be reached between 8.30 AM- 5 PM. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, John R. Lee can be reached on (571) 272-2477.

Zia Hashmi

September 22, 2004

SUPER/IISORY PATENT EXAMINER
TECHNOLOGY CENTER 2800